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Pas 5500 Wafer

Alignment And Zero

Exposure Coat

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From the ASML archives: \"PAS 5500 - The Inside Story\" (1993) ASML and UC San Diego: The first ever virtual course on EUV lithography **The Extreme Physics Pushing Moore's Law to the Next Level**

ASML - Powering the Next Phase of Semiconductor Manufacturing *EUV:*

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Lasers, plasma, and the sci-fi tech that will make chips faster | Upscaled

Photolithography: Step by step

Maskless Photolithography Stepper for Homemade Chips

ASML EUV in action How Microchips are made *From Sand to Silicon: the Making of a Chip | Intel* **ASML and**

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Carl Zeiss - Two Companies, one business

Photolithography Process How Chips are Manufactured — with Optics from ZEISS A Day in the Life of ASML's Customer Support Engineer — US

Maskless Photolithography with DLP Projector - 10um Feature Sizes

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**Welcome to ASML Wilton, CT, USA
TRUMPF EUV lithography – This all
happens in one second How
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Photolithography Basics Inside The
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Factory - BBC Click [A visit to ASML's
cleanroom for EUV ASML in 1 minute](#)**

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**30 Years of ASML - From Shed To
World Leader** How Extreme

Ultraviolet Lithography works | Part 1/3

Our Stories - Steef Wittekoek about

the early days of ASML Optics at

ASML Wilton ~~Erik Loopstra~~

~~Vadim Banine~~ Extreme ultraviolet

lithography **The Point: What's behind**

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ASML chip delay to China? ASML:

Verkleinen chips is grote kunst Lecture

~~40 (CHE 323) Lithography Imaging~~

~~Tools~~ *Projection lithography.wmv*

Introduction To Asml Pas 5500

The first step & Scan system

introduced by ASML was the PAS

5500/500, completed in 1997 and

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shipping in volume from 1998. See for instance, ASML's 20th anniversary book, REFLECT & IMAGINE - 20 Years of ASML' published by ASML in December 2004.

ASML - PAS 5500/400, Step & Scan System

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As Architect PAS 5500 Electronics you specify the new rack design, manage the design outsourcing, align the design with the Software Development team, manage the system integration and transfer the new design to Customer Support (CS), Manufacturing and Logistics. Job

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Description. The Architect PAS 5500 Electronics is responsible for the following:

Architect PAS 5500 Electronics - ASML

Description. The PAS 5500/850C 248-nm Step-and-Scan system

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enables 110-nm mass production. And

Since the initial introduction of the PAS 5500/850, the PAS 5500/850 series

have become the worldwide standard for both 110-nm logic and 110-nm

memory applications. The PAS

5500/850C can be configured with a number of options that enable ultra low-

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5500 Wafer Alignment And
Zero Exposure Coat
k 1in manufacturing, extending
application of the PAS 5500/850C well
below 110 nm.

PAS 5500/850C - ASML

The ASML PAS 5500/350C stepper is a photolithography equipment, using DUV light from a KrF laser source (248

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nm) to expose photoresist through a mask, generally referred as the “reticle”. In opposition to a contact/proximity mask-aligner, a projection lens is interposed between the reticle and the wafer in order to reduce (usually by 4x or 5x) the image of the reticle onto the wafer.

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5500 Wafer Alignment And

ASML PAS 5500/350C ? CMI ? EPFL

Architect PAS 5500 Electronics -

asml.com The PAS 5500/850C

248-nm Step-and-Scan system

enables 110-nm mass production.

Since the initial introduction of the PAS

5500/850, the PAS 5500/850 series

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5500 Wafer Alignment And Zero Exposure Coat
have become the worldwide standard for both 110-nm logic and 110-nm memory applications.

Introduction To Asml Pas 5500 Wafer Alignment And Zero ...

The ASML PAS 5500/60 stepper is an i-line system with automatic 100mm *

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5500 Wafer Alignment and
Zero Exposure Coat
wafer cassette processing capability.

Using 365nm near-UV light this stepper is capable of a minimum feature size of 450nm and alignment between lithographic layers of 90nm. The stepper uses 5X reduction imaging allowing a maximum die area of 18mm by 22.4mm per exposure.

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5500 Wafer Alignment And

**ASML PAS 5500/60 i-line Stepper
(asml) | Stanford ...**

The ASML PAS 5500/350C stepper is a photolithography equipment, using DUV light from a KrF laser source (248 nm) to expose photoresist through a mask, generally referred as the

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“reticle”. In opposition to a contact/proximity mask-aligner, a projection lens is interposed between the reticle and the wafer in order to reduce (usually by 4x or 5x) the image of the reticle onto the wafer.

ASML PAS 5500/350C ? Center of

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MicroNanotechnology CMI ? EPFL

Lithography Using ASML Stepper

Page 5 INTRODUCTION (cont.) The ASML PAS 5500 uses wafer alignment marks that are diffraction gratings. There are marks for both the x and y directions. These marks are illuminated with a HeNe laser at a

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single wavelength near 632.8nm. The reflected wave exhibits a diffraction pattern of bright

Lithography Using ASML Stepper - diyhpl

ASML : ASM Lithography - PAS
5500/400, Step & Scan System -

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ASML's Total Step and Scan Solution
for sub 0.25Um Applications

ASML - PAS 5500/400, Step & Scan System specification

Within the year, we launched a
breakthrough platform, the PAS 5500.
With its industry-leading productivity

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and resolution, the PAS 5500 brought on board the key customers that ASML needed to turn a profit. It was a first step to maturity. In 1995, ASML became a fully independent public company, listed on the Amsterdam and New York stock exchanges.

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Our history | ASML - Supplying the semiconductor industry

The PAS 5500/750F DUV Step-and-Scan system enables 130-nm mass production using mature 248-nm KrF technology.

PAS 5500/750F - asml.com

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INTRODUCTION (cont.) The ASML PAS 5500 uses wafer alignment marks that are diffraction gratings. There are marks for both the x and y directions. These marks are illuminated with a HeNe laser at a single wavelength near 632.8nm.

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**ROCHESTER INSTITUTE OF
TECHNOLOGY MICROELECTRONIC**

...

Within BL MPS, Design & Engineering deliver the structural solution to supports PAS 5500 installed base by providing refurbished systems, upgrades, spare-parts and service to

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our customers. To extend the support of the PAS 5500 to 2030 and possibly longer, BL MPS will do a full redesign of the PAS 5500 electronics.

**Embedded Software Design
Engineer (C, VxWorks, ARM ... -
ASML**

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Since the initial introduction of the PAS 5500/850, the PAS 5500/850 series have become the worldwide standard for both 110-nm logic and 110-nm memory applications. The PAS 5500/850D can be configured with a number of options that enable ultra low-k 1 in manufacturing, extending

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application of the PAS 5500/850D well below 110 nm.

**PAS 5500/850D Datasheet -- ASML
Optics -- Lithography ...**

The National Nanotechnology
Infrastructure Network is supported by
National Science Foundation

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Cooperative Agreement
EECS-0335765 and by support from
the member institutions.

ASML PAS 5500/60 I-line Stepper | National Nanotechnology ...

3.1 Overview- These instructions
provide an overview of creating

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stepper jobs for the ASML PAS And
5500/200. Up to 30 layers can be done
in a single job. In a job, Wafer
Layout will define how the die are
arranged on the wafer and Layer
Layout will define the details of each
layer. The maximum square field size
on the wafer is $X=22\text{mm}$ and

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Semiconductor & Microsystems

4.1 General Description - The ASML PAS 5500/200 is a 5x reduction, i-line stepper set up for exposure of 6 inch wafers using 6 inch reticles. The system has 350nm resolution with a

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0.48-0.60 variable numerical aperture.
The maximum field size on the wafer
is 22x22mm. Overlay capability is
better than 50nm.

R.I.T Title: ASML Stepper

Lithography System -- PAS

5500/400D: The PAS 5500/400D i-line

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Step-and-Scan system has a variable-NA (0.48 to 0.65) 4x projection lens, which, combined with ASML's AERIAL Illuminator, provides 280-nm resolution. ASML's revolutionary Step-and-Scan stage technology enables...

ASML Optics Lithography

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**Equipment Data Sheets |
Engineering360**

This projection printer uses a DUV (248nm) lens column (0.63 N.A.) to provide a 4:1 reduction with an exposure field size up to 22mm square. Minimum feature size is <math><0.20\mu\text{m}</math>.

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